

**Search Notes**

Application No.

10/670,520

Examiner

Stephen W. Smoot

Applicant(s)

ASAKAWA ET AL.

Art Unit

2813

**SEARCHED**

Class	Subclass	Date	Examiner
257	775	6/24/2004	SWS
257	E23.169	6/24/2004	SWS
257	E23.174	6/24/2004	SWS
174	262	6/24/2004	SWS
200	264	6/24/2004	SWS
428	550	6/24/2004	SWS
428	566	6/24/2004	SWS
430	5	6/24/2004	SWS
430	269	6/24/2004	SWS
Updated	Above	11/9/2004	SWS

*S.W.S.**S.W.S.***INTERFERENCE SEARCHED**

Class	Subclass	Date	Examiner
Same as Above		11/9/2004	<i>S.W.S.</i> SWS

**SEARCH NOTES  
(INCLUDING SEARCH STRATEGY)**

	DATE	EXMR
Considered all references cited in parent application.	6/24/2004	<i>S.W.S.</i> SWS
Key Words: Porous Material - Pores, Voids, Substrate; Mask, Photomask;	6/24/2004	<i>S.W.S.</i> SWS
Conductor, Metal - Infiltrate, Impregnate, Via, Feedthrough, Trace, Throughhole, Interconnect, Wiring.	6/24/2004	<i>S.W.S.</i> SWS
Updated Above Search	11/9/2004	<i>S.W.S.</i> SWS
Search Tools - EAST (attached): USPAT; US PG PUBS; Derwent; EPO; JPO; IBM TDB	6/24/2004 <i>11-9-04</i>	<i>S.W.S.</i> SWS <i>S.W.S.</i>